



Solutions for a nanoscale world.™



NanoScale Metrology Workshop

Wednesday April 27th

Helsinki Fair Center

Timetable

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| 13:30 | Freek Pasop , Strategic Sales Development Manager Optical Metrology, Veeco Instruments
<i>Stylus and Optical Metrology for Printed Electronics</i> |
| 14:00 | Patrick Markus , Applications Engineer, Veeco Instruments
<i>Nanolithography as a Tool for Creating Nanostructures</i> |
| 14:30 | Coffee break |
| 15:00 | Patrick Markus , Applications Engineer, Veeco Instruments
<i>Local Electrical Characterization Methods using Scanning Probe Microscopy</i> |
| 15:30 | Patrick Markus , Applications Engineer, Veeco Instruments
<i>Practical Demonstrations of Optical Metrology, SPM and Nanolithography</i> |
| 16:00 | Closing |

- 1- Courtesy of Carla Passmore, H. Stranix, H.P. Corvallis, Hewlett Packard, Oregon, USA
- 2- Courtesy Philips PolyLED
- 3- Courtesy of O. Hellwig, BESSY GmbH, Berlin, Germany, M. Best and E.E. Fullerton, San Jose Research Center, HGST, San Jose, CA, USA
- 4- Courtesy Z. Xi, E. Luo, J. Xu, I. Wilson, B. Sundareval, The Chinese University of Honk Kong, China
- 5- Courtesy of Sergei V. Kalinin (Oak Ridge National Laboratory), Stephen Jesse (University of Tennessee and ORNL), Junsoo Shin (UT and ORNL), Arthur P. Baddorf (ONRL), David Geohegan (ORNL)